

AMENDMENTS TO THE CLAIMS

1. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol and at least two inorganic acids, wherein one of said inorganic acids is selected from the group consisting of sulfuric acid, boric acid, carbonic acid, perchloric acid and sulfurous acid.

2. (Currently amended) ~~The composition according to claim 1, wherein said alcohol is~~ An etching composition consisting essentially of:

a non-aqueous composition of a polyhydric alcohol and at least two inorganic acids, wherein one of said inorganic acids is selected from the group consisting of sulfuric acid, boric acid, carbonic acid, perchloric acid and sulfurous acid.

3. (Original) The composition according to claim 2, wherein said polyhydric alcohol is selected from the group consisting of ethylene glycol, propylene glycol, butylene glycol, dipropylene glycol, sorbitol, hexylene glycol, 1,3-dibutylene glycol, 1,2,6-hexanetriol and 1,5-pentanediol.

4. (Previously presented) The composition according to claim 2, wherein said polyhydric alcohol is selected from the group consisting of ethylene glycol and propylene glycol.

5. (Original) The composition according to claim 1, wherein said alcohol is propylene glycol.

6. (Original) The composition according to claim 1, wherein said alcohol is a C₂-C₆ alcohol.

Claims 7-8. (Canceled)

9. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol and at least two inorganic acids, wherein said inorganic acids are selected from the group consisting of nitric acid, phosphoric acid, sulfuric acid, boric acid, carbonic acid, perchloric acid and sulfurous acid.

Claims 10-12. (Canceled)

13. (Previously presented) The composition according to claim 1, wherein the volume ratio of alcohol to a first acid to a second acid is from about 10-50:5-40:1.

14. (Previously presented) The composition according to claim 13, wherein the volume ratio of alcohol to said first acid to said second acid is from about 20-40:10-30:1.

15. (Previously presented) The composition according to claim 14, wherein the volume ratio of alcohol to said first acid to said second acid is about 30:20:1.

Claims 16-21. (Canceled)

22. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol and at least two different inorganic acids selected from the group consisting of phosphoric acid, sulfuric acid, boric acid, carbonic acid, perchloric acid and sulfurous acid.

23. (Original) ~~The composition according to claim 22, wherein said alcohol is~~
An etching composition consisting essentially of:

a non-aqueous composition of a polyhydric alcohol and at least two different inorganic acids selected from the group consisting of phosphoric acid, sulfuric acid, boric acid, carbonic acid, perchloric acid and sulfurous acid.

24. (Original) The composition according to claim 23, wherein said polyhydric alcohol is selected from the group consisting of ethylene glycol, propylene glycol, butylene glycol, dipropylene glycol, sorbitol, hexylene glycol, 1,3-dibutylene glycol, 1,2,6,-hexanetriol and 1,5-pentanediol.

25. (Previously presented) The composition according to claim 23, wherein said polyhydric alcohol is selected from the group consisting of ethylene glycol and propylene glycol.

26. (Original) The composition according to claim 22, wherein said alcohol is propylene glycol.

27. (Original) The composition according to claim 22, wherein said alcohol is a C₂-C₆ alcohol.

Claims 28-32. (Canceled)

33. (Previously presented) The composition according to claim 22, wherein the volume ratio of alcohol to a first acid to a second acid is from about 10-50:5-40:1.

34. (Previously presented) The composition according to claim 33, wherein the volume ratio of alcohol to said first acid to said second acid is from about 20-40:10-30:1.

35. (Previously presented) The composition according to claim 34, wherein the volume ratio of alcohol to said first acid to said second acid is about 30:20:1.

Claims 36-38. (Cancelled)

39. (Currently amended) A composition for etching doped polysilicon from a silicon substrate with high selectivity to undoped polysilicon consisting essentially of:

~~a non-aqueous composition comprising~~ propylene glycol, nitric acid and hydrofluoric acid in a volume ratio of propylene glycol to nitric acid to hydrofluoric acid from about 10-50:5-40:1.

40. (Previously presented) The composition according to claim 39, wherein the volume ratio of propylene glycol to nitric acid to hydrofluoric acid is from about 20-40:10-30:1.

41. (Previously presented) The composition according to claim 39, wherein the volume ratio of propylene glycol to nitric acid to hydrofluoric acid is about 30:20:1.

Claims 42-82. (Canceled)

83. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of propylene glycol and at least two inorganic acids, wherein one of said inorganic acids is selected from the group consisting of hydrofluoric acid, phosphoric acid, sulfuric acid, boric acid, carbonic acid, perchloric acid and sulfurous acid.

Claim 84-88. (Canceled)

89. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol, sulfuric acid, and at least another inorganic acid.

90. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol, boric acid, and at least another inorganic acid.

91. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol, perchloric acid, and at least another inorganic acid.

92. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol, carbonic acid, and at least another inorganic acid.

93. (Previously presented) An etching composition consisting essentially of:

a non-aqueous composition of an alcohol, sulfurous acid, and at least one inorganic acid.